## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Patent Application Serial No	Unknown
Filing Date	Filed Herewith
Inventor	Weimin Li et al.
Assignee	Micron Technology, Inc.
Group Art Unit	Unknown
Examiner	
Attorney Docket No	MI22-2274
Customer No.	021567
Title: Methods of Depositing Silicon Dioxide	
Fabrication of Integrated Circuitry, Methods	
and Methods of Forming Arrays of Memory	Cells

## SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

References -- See Attached Form PTO-1449

The attached form PTO-1449 is submitted in compliance with 37 CFR §1.56. Pursuant to 1276 OG 55, August 5, 2003, no copies of cited U.S. patents or U.S. patent application publications are included, as the date of filing of this patent application occurs after June 30, 2003. No admission is made regarding whether all the listed references are prior art.

Respectfully submitted,

Dated: 3-22-04

Mark S. Matkin Reg. No. 32,268

APPLICANT: Weimin Michael Li et al.

Form PTO-1449

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ATTY. DOCKET NO. MI22-2274

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LIST OF ART CITED BY APPLICANT

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**GROUP** Unknown

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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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